

EE 207: MidSem Exam

Date: 15/09/2018, Duration - 2 hrs

Note: In case of any ambiguity/apparent inconsistency/missing parameters, make appropriate assumptions. Provide justifications to your assumptions and solve the problem. **Do not ask!**

Relevant parameters:

Parameter	Value
n_i (for Silicon)	10^{10} cm^{-3}
T	300K
kT/q	0.0256V
Electron mobility	$1000 \text{ cm}^2/\text{Vs}$
Hole mobility	$400 \text{ cm}^2/\text{Vs}$
Dielectric permittivity of Si	$11.8 \times 8.854 \times 10^{-14} \text{ F/cm}$
Band gap of Si	1.12eV

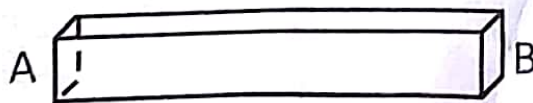
$$\frac{F \times V + \text{cm}^3}{\text{cm}^2}$$

Question 1 (3 marks)

- A. The electron density of a sample of intrinsic silicon is 10^{15} cm^{-3} . Estimate the hole density.
- B. For a silicon sample with $N_A = 10^{17} \text{ cm}^{-3}$, find the electron and hole densities (1 mark)
- C. Under some excitation, a Silicon sample has an excess electron density of 10^{12} cm^{-3} . Assuming charge neutrality conditions, estimate the excess hole density (1 mark)

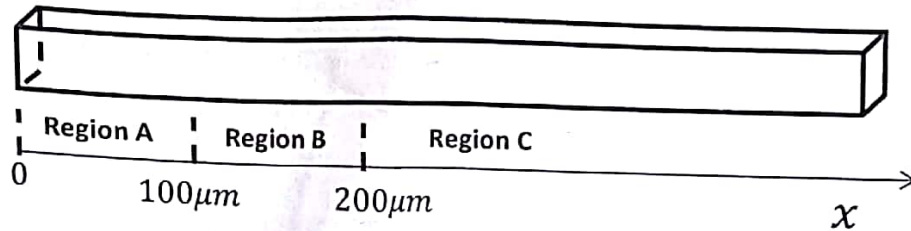
Question 2 (4 marks):

- (a) The conductivity of a p-type doped Si sample of length $L = 10 \mu\text{m}$ is 32 S/cm . Estimate the doping density (1 mark)
- (b) Draw the E-B diagram of the sample under a bias of 1 V. Assume $\Delta n = \Delta p = 0$ at both the Silicon-metal contacts and neglect diffusion. Also indicate the electric field (1 mark)
- (c) Consider a p-typed doped Si sample with length L . All the faces of the sample (see below) are characterized by electron hole recombination with the rate of reaction being given as $\frac{dn}{dt} = -S\Delta n$, where S is a constant. It is given that $S = 0$ for all faces except A and B. For low level injection scenario due to uniform illumination, estimate the effective minority carrier lifetime subject to the following conditions: (i) Consider only SRH recombination and neglect radiative recombination. (ii) Neglect any spatial variation in carrier densities. (2 marks.)



Question 3 (7 marks):

A semi-infinite p-type Si sample consists of three regions whose properties are listed below.

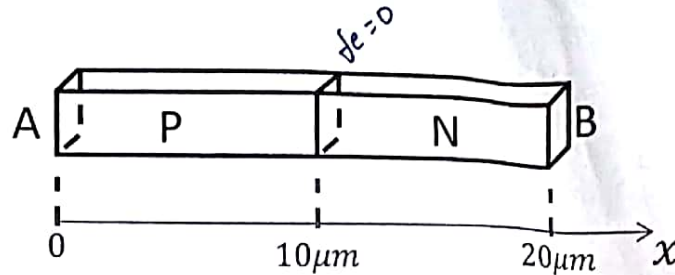


Region	Definition (also see Figure)	Lifetime	Generation
A	$0 \leq x < 100\mu m$	$\tau_n = \tau_p = \infty$	$G = 10^{18} cm^{-3} s^{-1}$
B	$100\mu m \leq x < 200\mu m$	$\tau_n = \tau_p = \infty$	$G = 0$
C	$x \geq 200\mu m$	$\tau_n = \tau_p = 1\mu s$	$G = 0$

The boundary condition at $x = 0$ is given by $\frac{dn}{dx} = 0$. Assuming steady state and low level injection conditions, answer the following:

- Making use of the boundary conditions at $x = 0$ and at $x = \infty$, provide appropriate expressions for electron density in the three regions (3 marks. Use the least number of unknown variables).
- Estimate the electron flux density at $x = 200\mu m$ (1 mark. Hint: You may want to avoid solving for all the unknown variables of part A).
- Using the information in part B, evaluate the carrier density profile for region C. Also indicate the carrier density at $x = 200\mu m$ (1 mark)
- With the information in part C, estimate the minority carrier density at $x = 100\mu m$ (1 mark)
- Using the information in part D, estimate the carrier density profile for region A. Indicate the carrier density at $x = 0$ (1 mark)

Question 4 (11 marks): A PN junction diode is shown below. The doping densities of the P and N regions are 10^{18} cm^{-3} and 10^{16} cm^{-3} , respectively. The boundary condition at both the faces A and B is $\Delta n = \Delta p = 0$. The carrier lifetime in the N region is given as $\tau_n = \tau_p = \infty$ (while that of the P region is to be estimated). Neglect any carrier recombination in the depletion region.



A. Estimate the width of depletion region under equilibrium conditions and the built-in potential (2 marks).

B. At some applied forward bias, we have the following information regarding the carrier flux density at the faces A and B. For the rest of the questions, you may ignore x_n and x_p , if required.

Face	Electron flux density	Hole flux density
A	0	$1.5 \times 10^{15} \text{ cm}^{-2} \text{ s}^{-1}$
B	To be estimated	$10^{15} \text{ cm}^{-2} \text{ s}^{-1}$

- (i) Using the above information and properties of the diode, estimate the applied bias (2 marks)
 - (ii) Estimate the minority carrier lifetime in the P type region (2 marks)
- C. Assume that the diode is under reverse bias with $V = -1 \text{ V}$ (the diode is still working properly and not in break-down conditions). Now, assume that the quasi-neutral N region is under uniform illumination with photons of energy 1.2 eV which results in a carrier generation rate of $G = 10^{16} \text{ cm}^{-3} \text{ s}^{-1}$. Estimate
- (i) electron and hole flux at face A (2 marks)
 - (ii) electron and hole flux at face B (2 marks)
 - (iii) current through the diode (1 mark)